

FIG. 1

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2/36

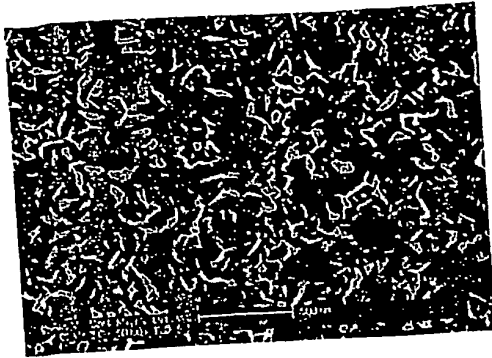


FIG. 2A

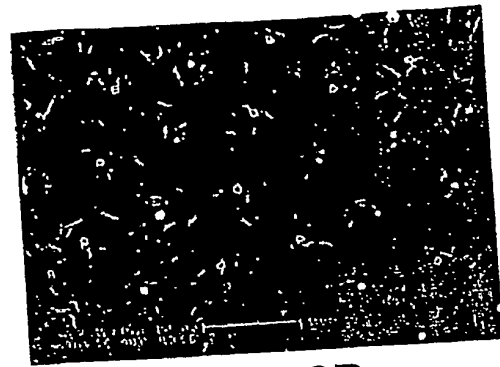


FIG. 2D



FIG. 2B



FIG. 2E

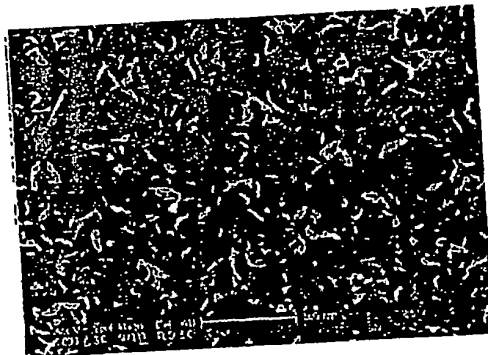


FIG. 2C

3/36

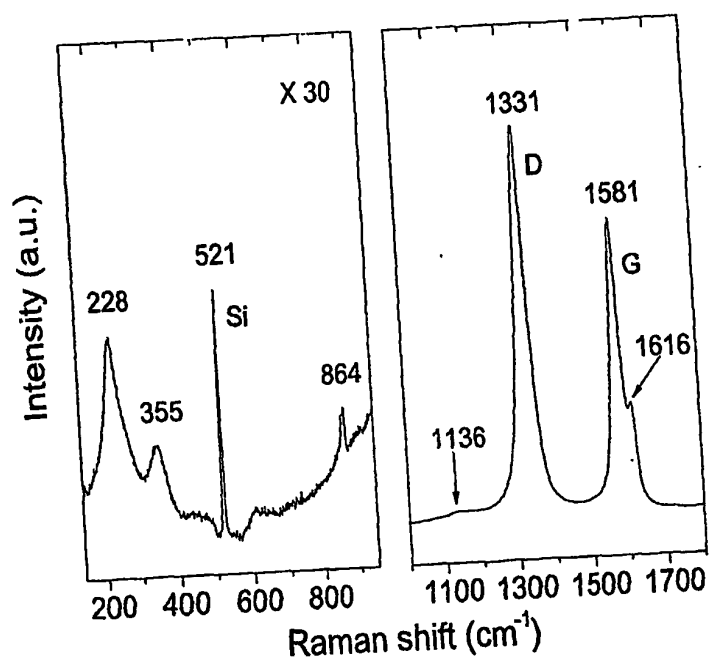


FIG. 3

4/36

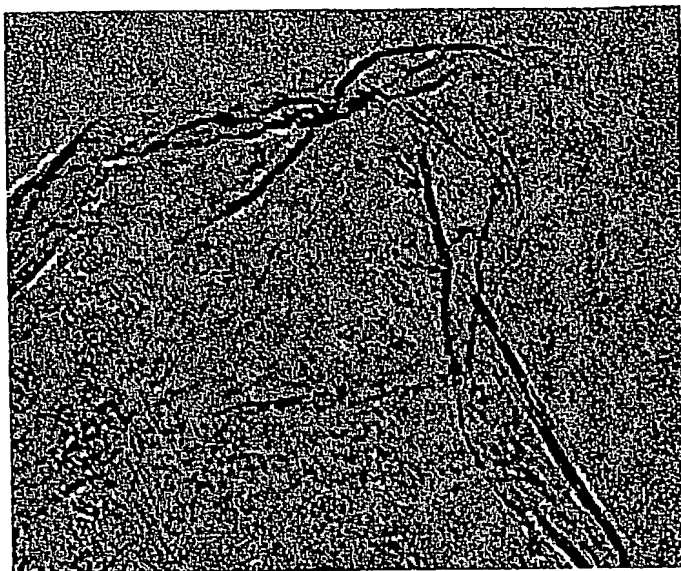


FIG. 4

5/36



FIG. 5A

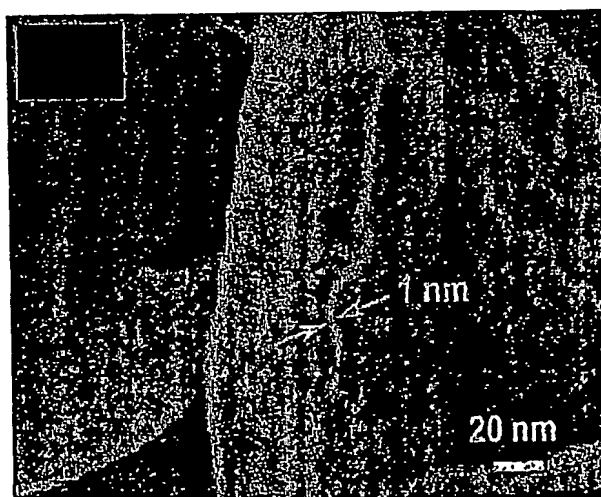


FIG. 5B

6/36

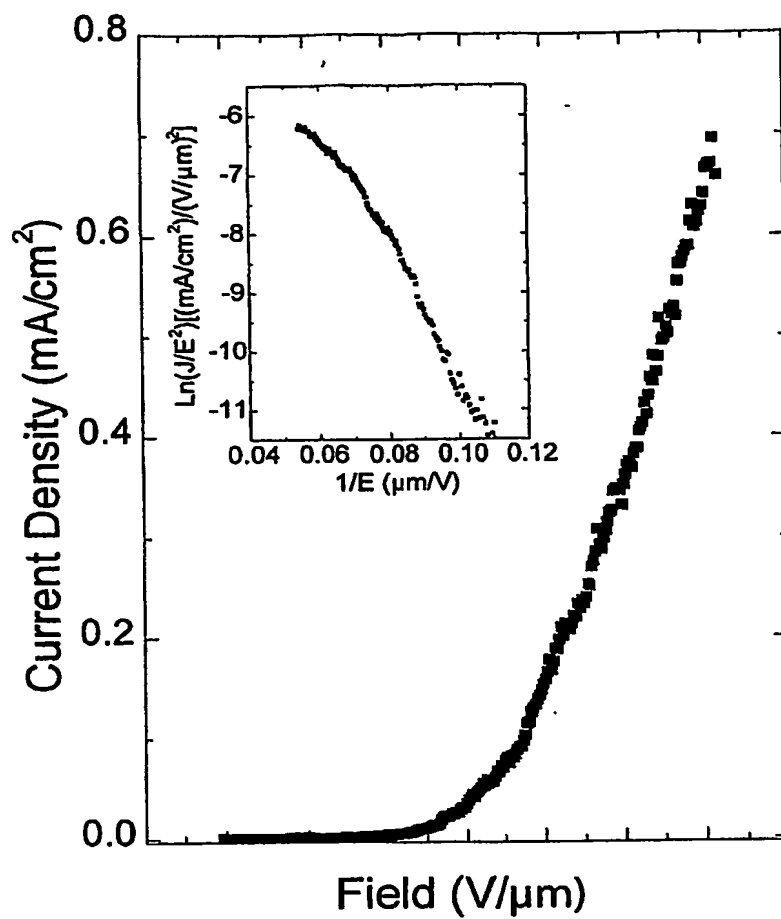


FIG. 6

7/36

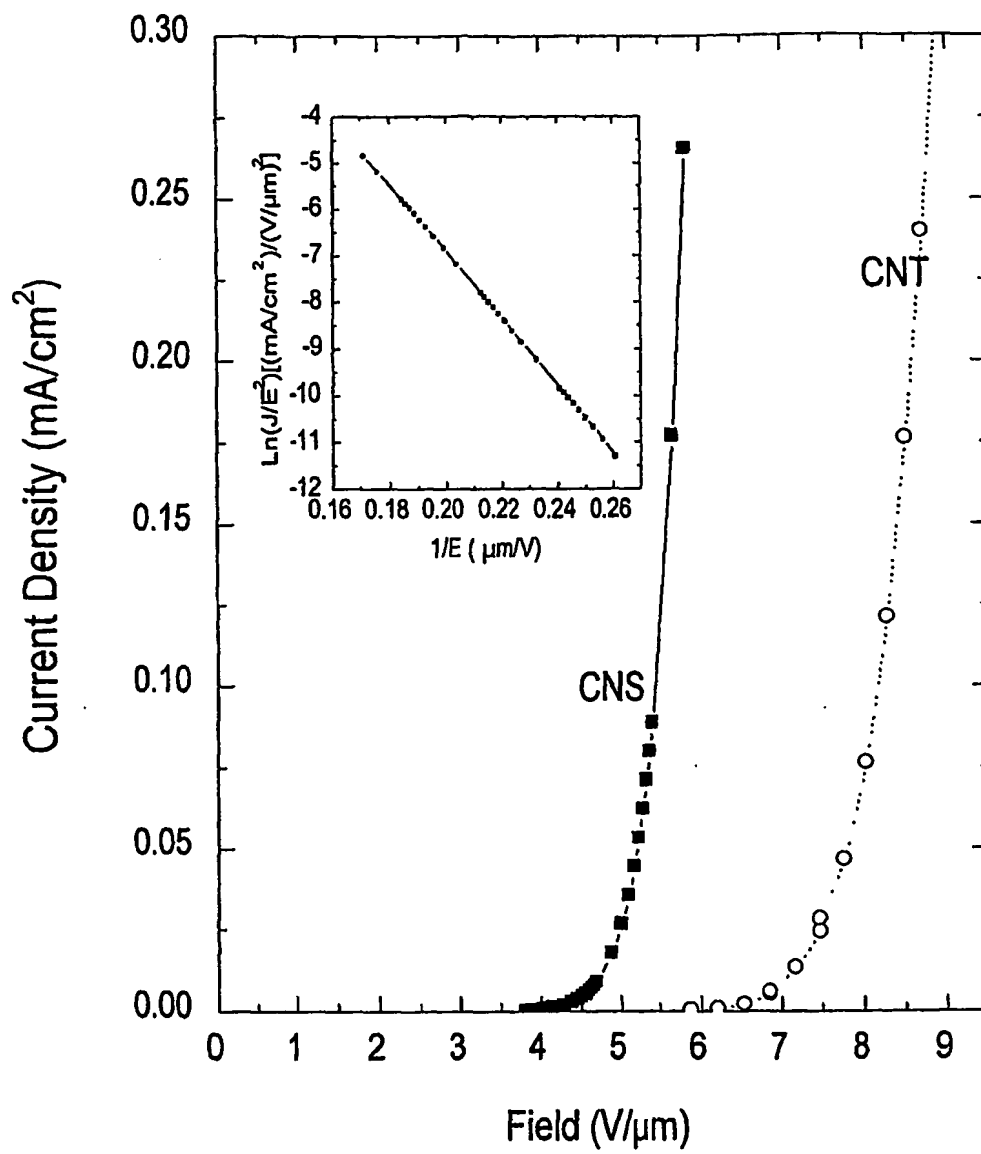


FIG. 7

8/36

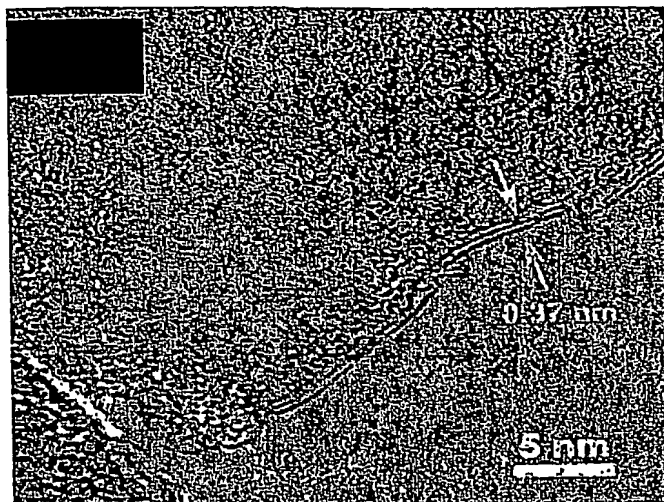


FIG. 8A

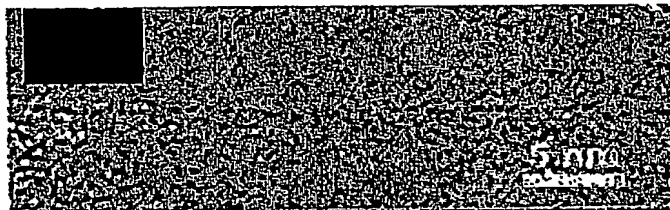


FIG. 8B

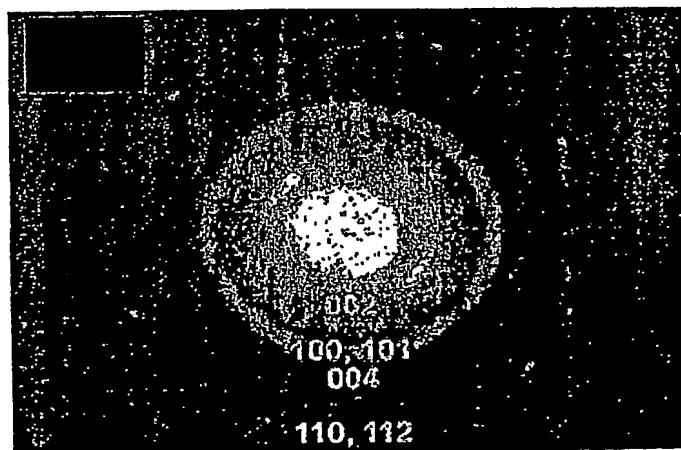


FIG. 8C

9/36

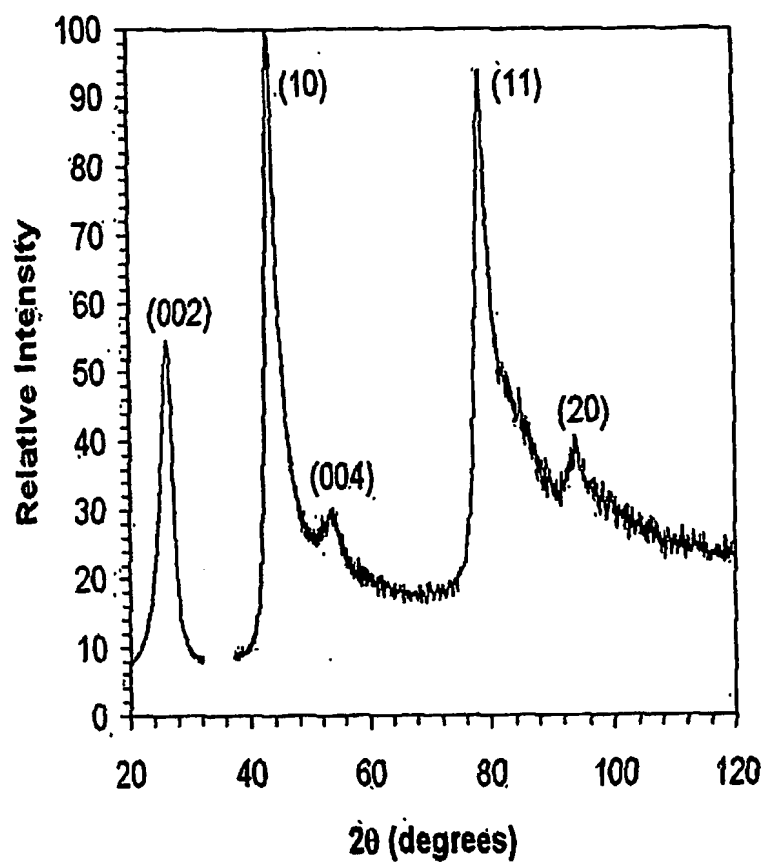


FIG. 9

10/36



FIG. 10A

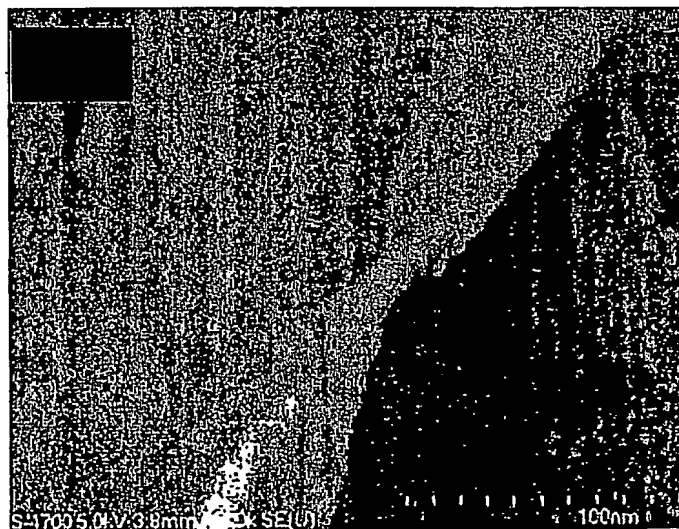


FIG. 10B

11/36

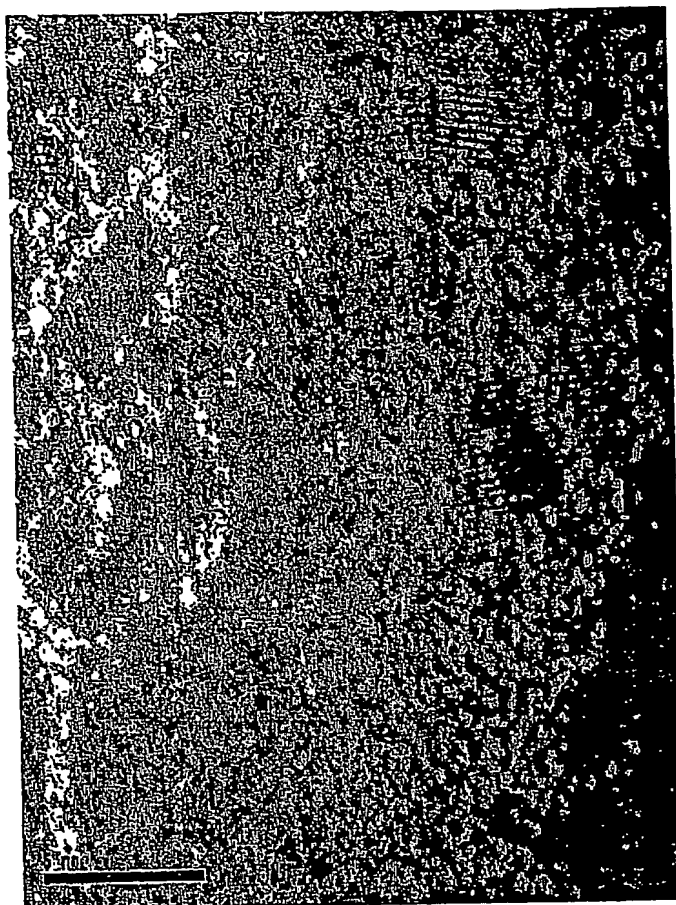


FIG. 11

12/36

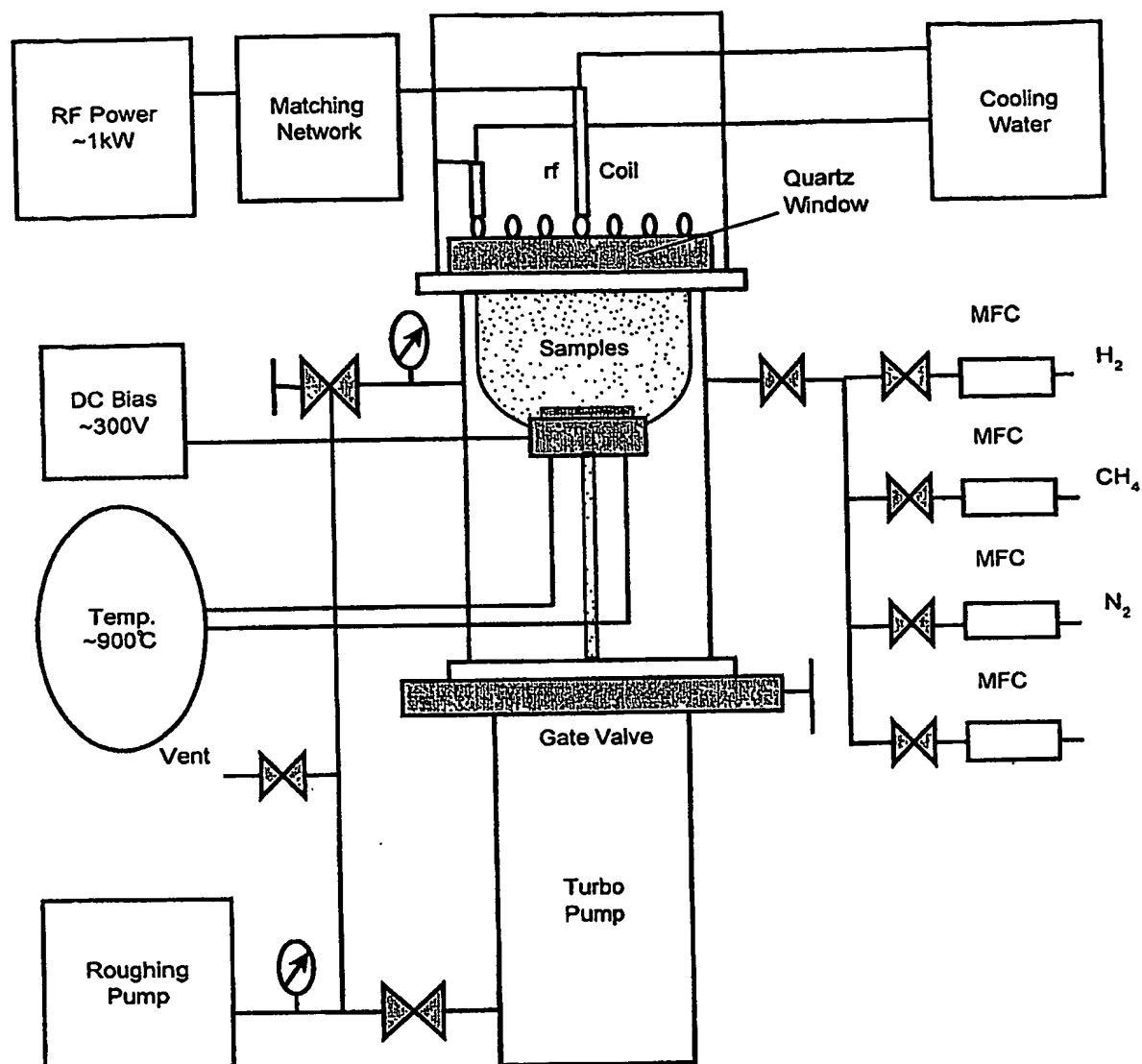


FIG. 12

13/36



FIG. 13A

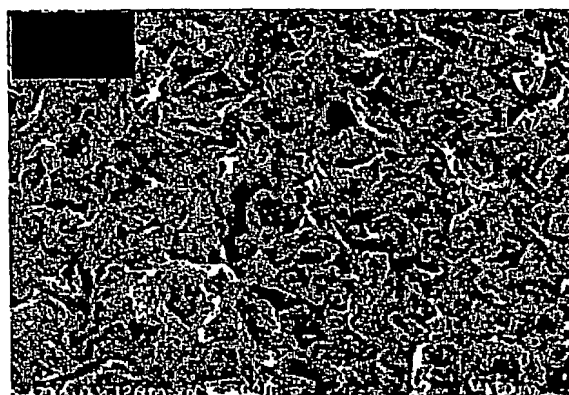


FIG. 13B



FIG. 13C

14/36



FIG. 14A



FIG. 14B



FIG. 14C

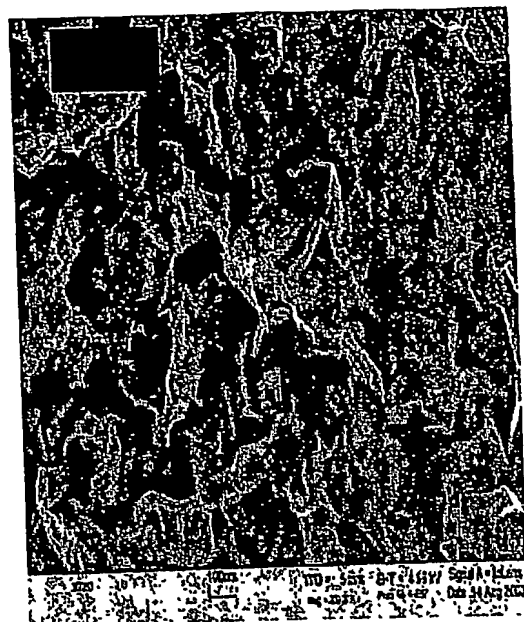


FIG. 14D

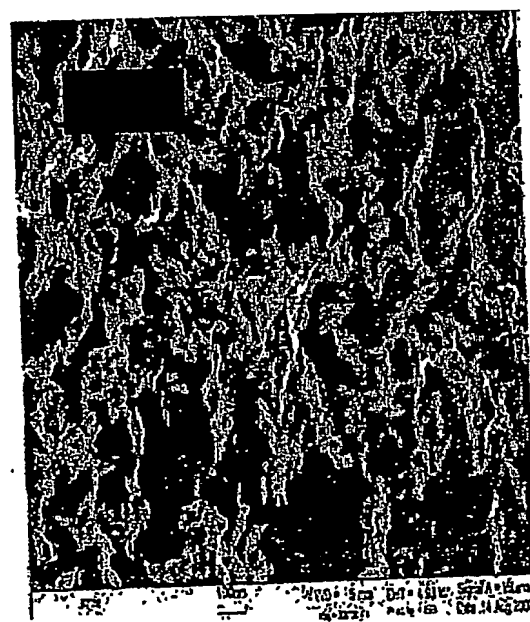


FIG. 14E

Nanosphere Lithography Approach to Carbon Nanotube

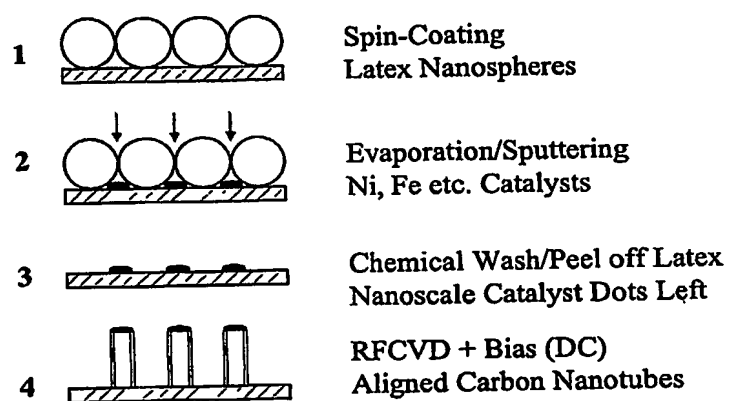
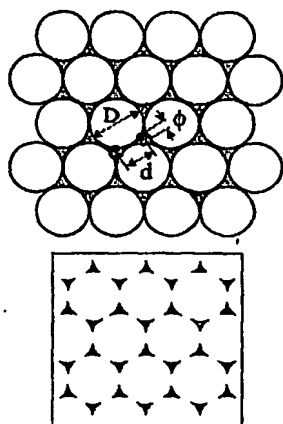


FIG. 15

16/36

Latex Nanosphere Lithography Pattern (Single-Layer)



Intersphere hole spacing:

$$d_{SL} = \frac{D}{\sqrt{3}} = 0.577D$$

Intersphere hole equivalent diameter:

$$\phi_{SL} = \left[\frac{4}{\pi} \cdot \left(\frac{1}{2} \cdot \frac{\sqrt{3}}{2} - \frac{1}{4} \cdot \frac{1}{6} \cdot 3 \cdot \pi \right) \right]^{\frac{1}{2}} D \approx 0.23D$$

D, nm	419	269	171	100
d_{SL}, nm	241	155	99	58
ϕ_{SL}, nm	96	62	39	23

FIG. 16

17/36

Comparison of SL and DL Patterns

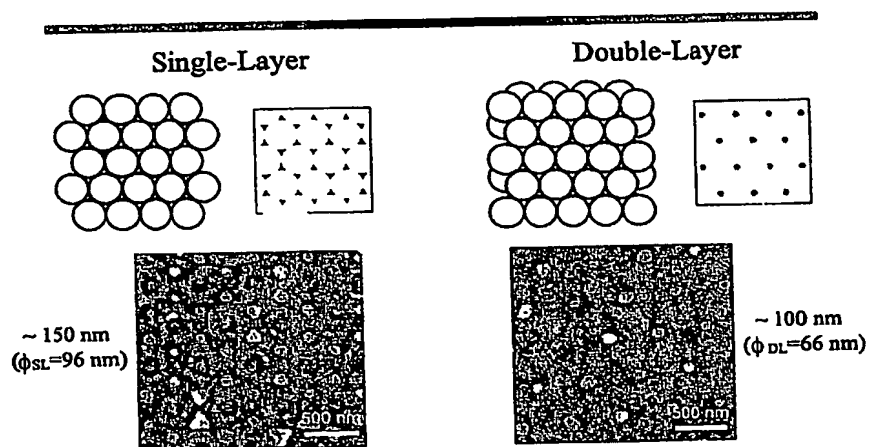
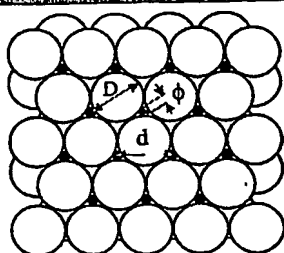


FIG. 17

18/36

Latex Nanosphere Double-Layer Pattern

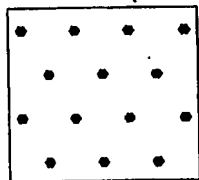


Intersphere hole spacing:

$$d_{DL} = D$$

Intersphere hole equivalent diameter:

$$\phi_{DL} \approx \left[\frac{4}{\pi} \cdot 6 \cdot \frac{1}{2} \cdot \frac{0.155}{2} \cdot 2 \cdot \lg 30 \cdot \frac{0.155}{2} \right]^{\frac{1}{2}} D \approx 0.16D$$

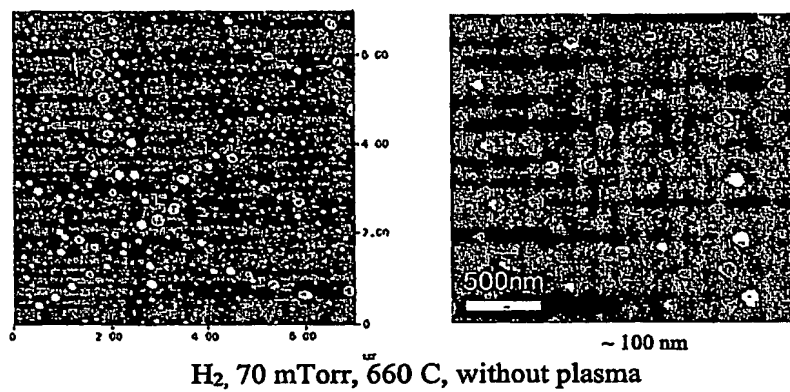


D, nm	419	269	171	100
d_{SL} nm	241	155	99	58
γ_{SL} nm	66	43	27	16

FIG. 18

19/36

Annealing of Ni Nanoscale Patterns - I Single-layer latex mask



H₂, 70 mTorr, 660 C, without plasma

FIG. 19

20/36

Annealing of Ni Nanoscale Patterns - II

Double-layer latex mask

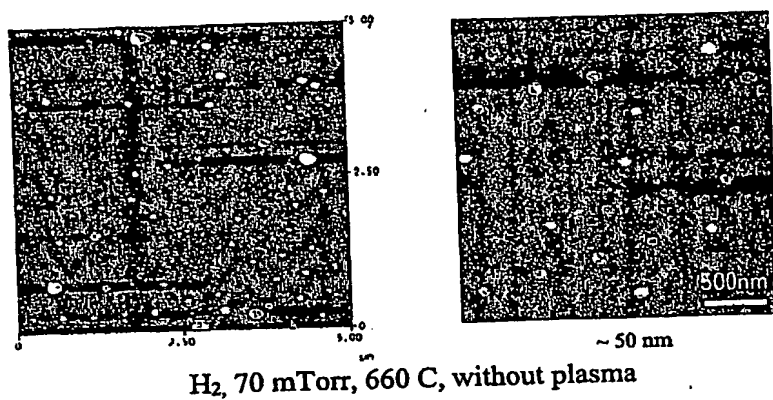


FIG. 20

21/36

Latex Nanosphere Masks (AFM Images)

Latex/Triton X-100/Methanol, Spin coating

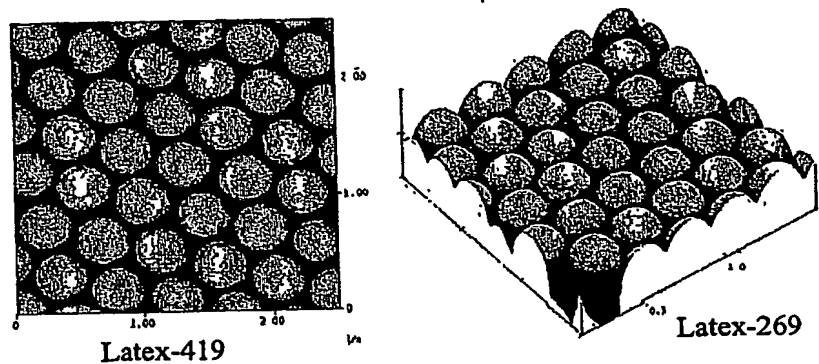


FIG. 21

22/36

Defects of Latex Nanosphere Mask

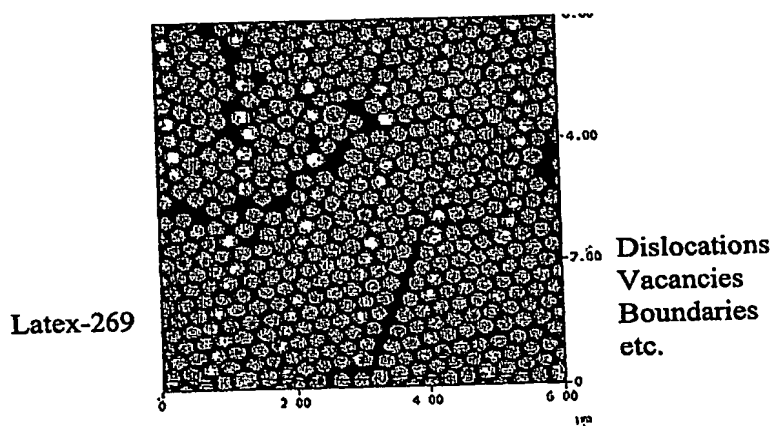


FIG. 22

23/36

Ni Pattern via E-Beam Evaporation
(20 nm, latex-419 mask)

Latex removed by CH_2Cl_2 or mechanical method

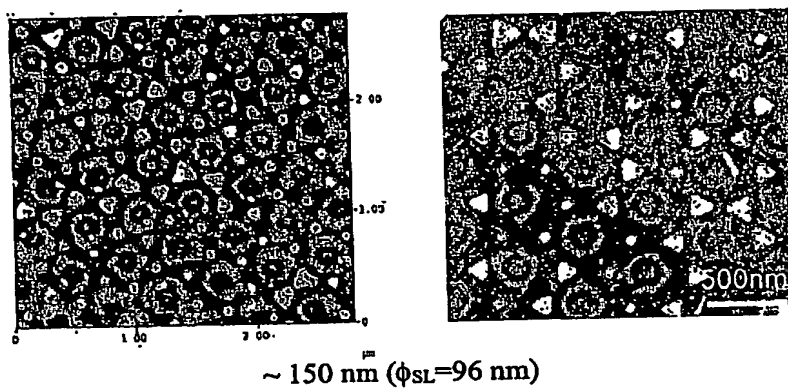


FIG. 23

24/36

Schematic of RF-CVD System

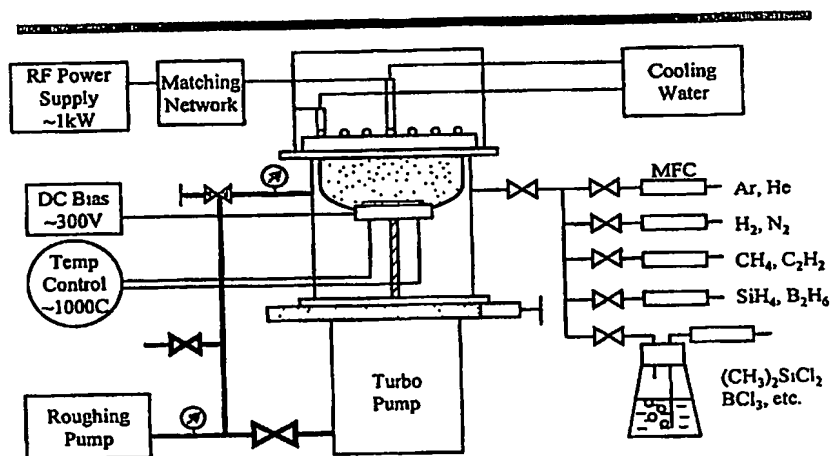


FIG. 24

25/36

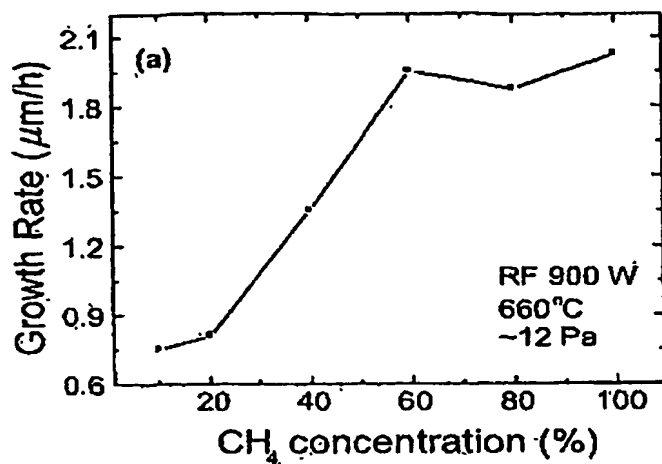


FIG. 25A

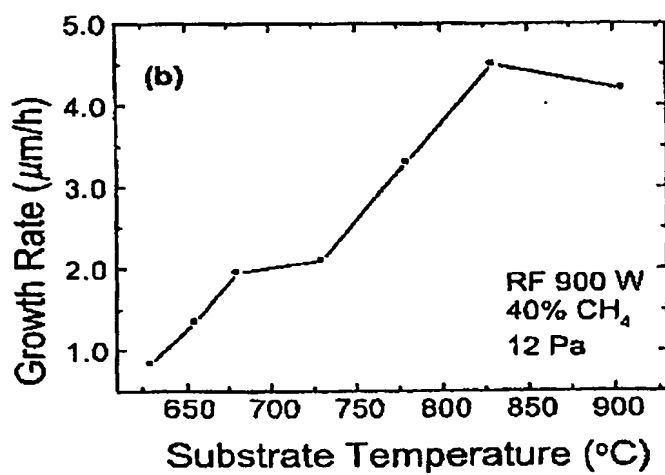


FIG. 25B

26/36

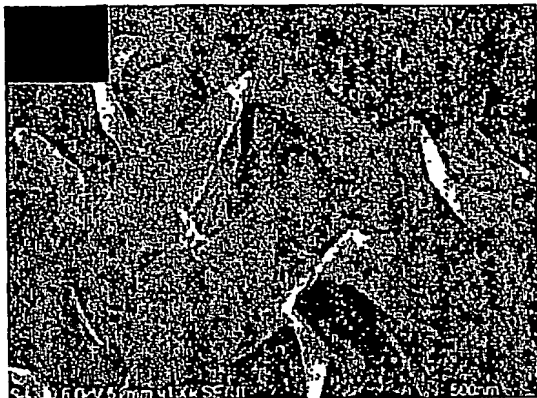


FIG. 26A

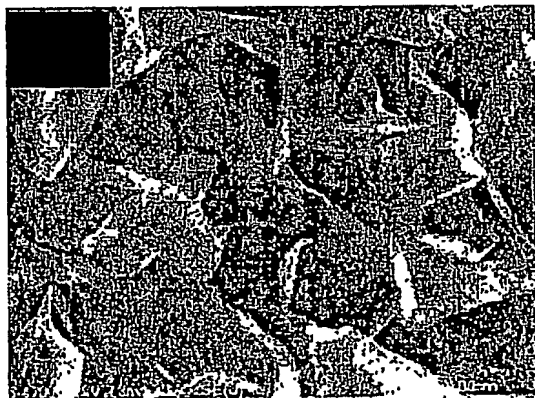


FIG. 26B

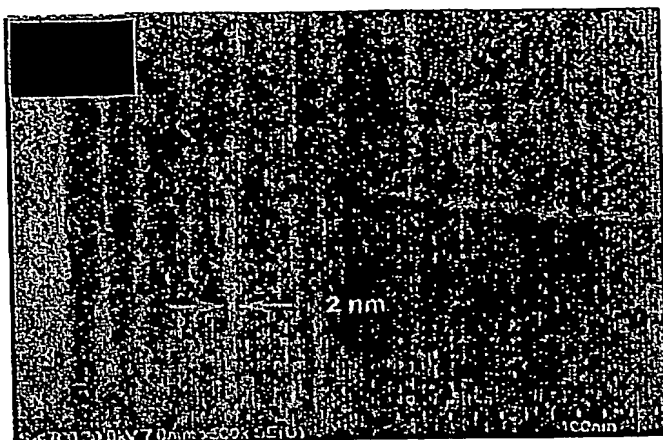


FIG. 27A

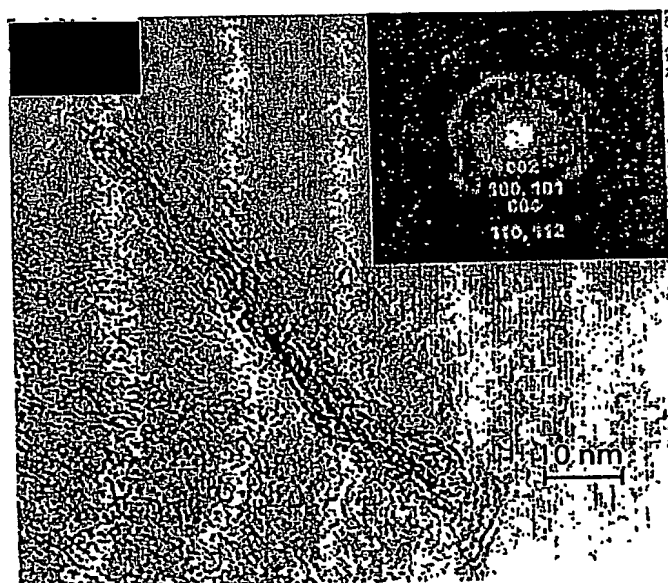


FIG. 27B

28/36

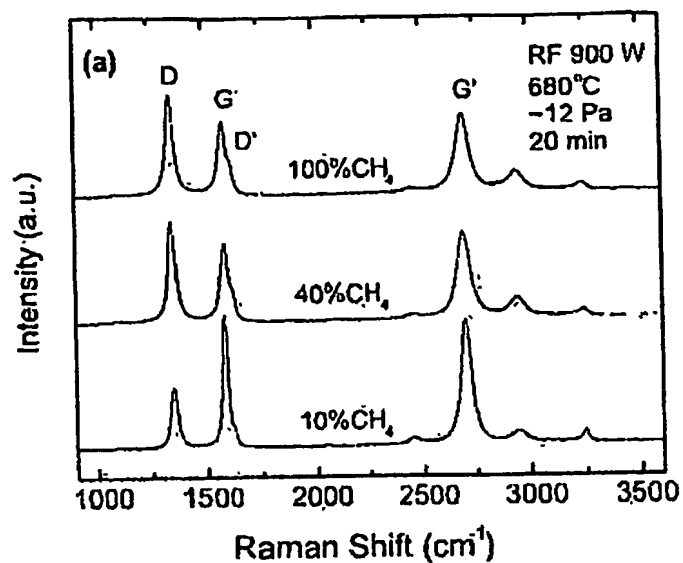


FIG. 28A

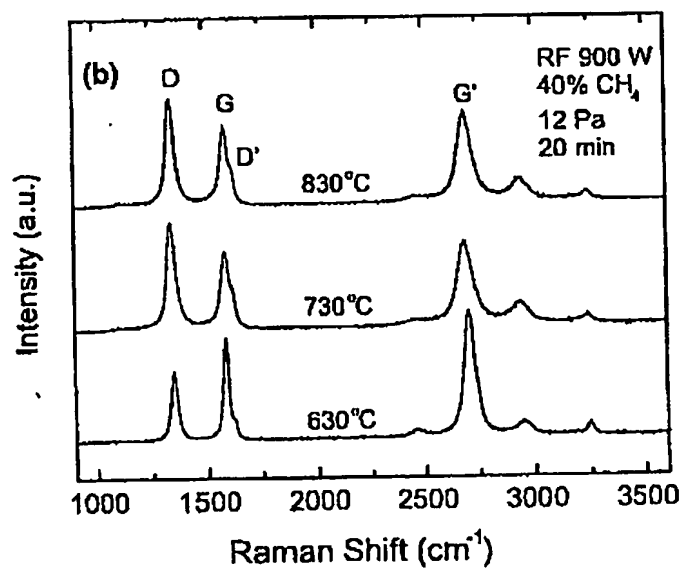


FIG. 28B

29/36

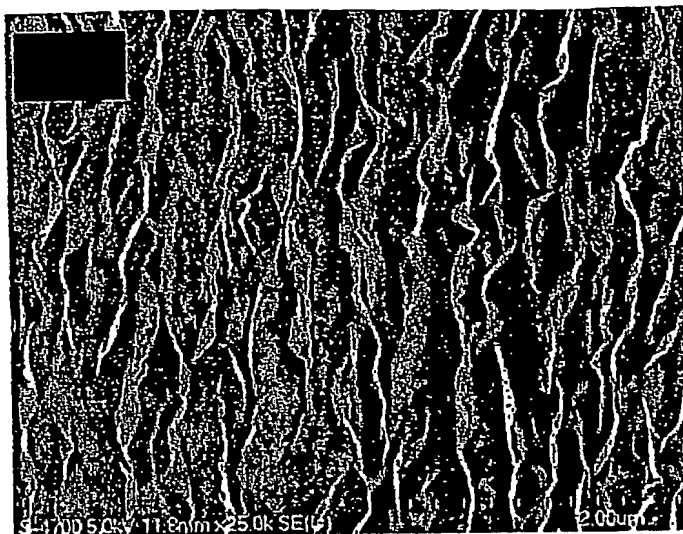


FIG. 29A

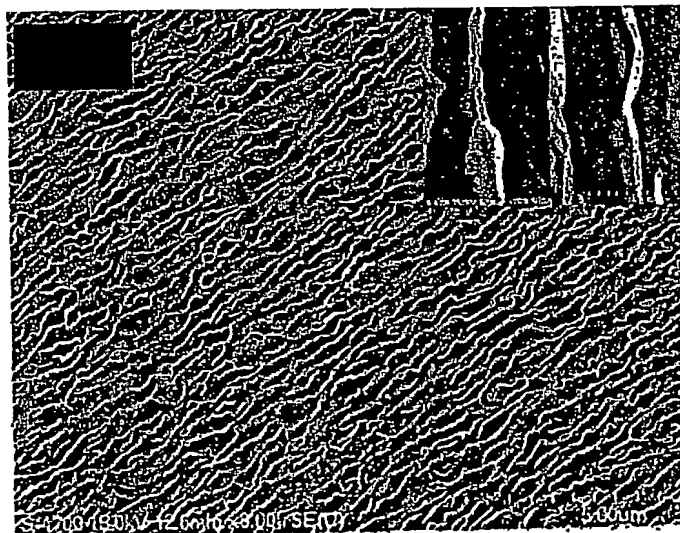


FIG. 29B

30/36



FIG. 30

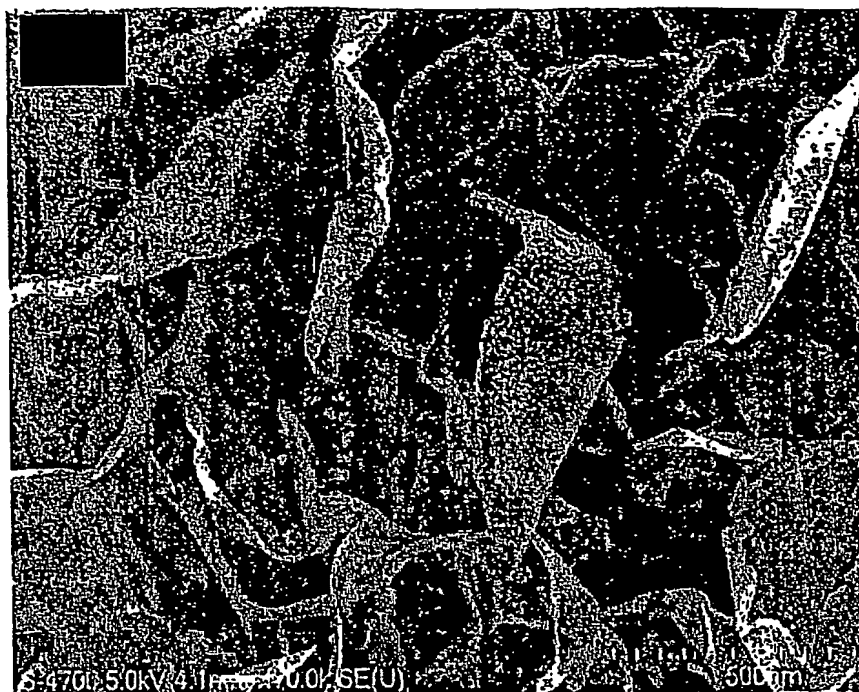


FIG. 31A



FIG. 31B

32/36

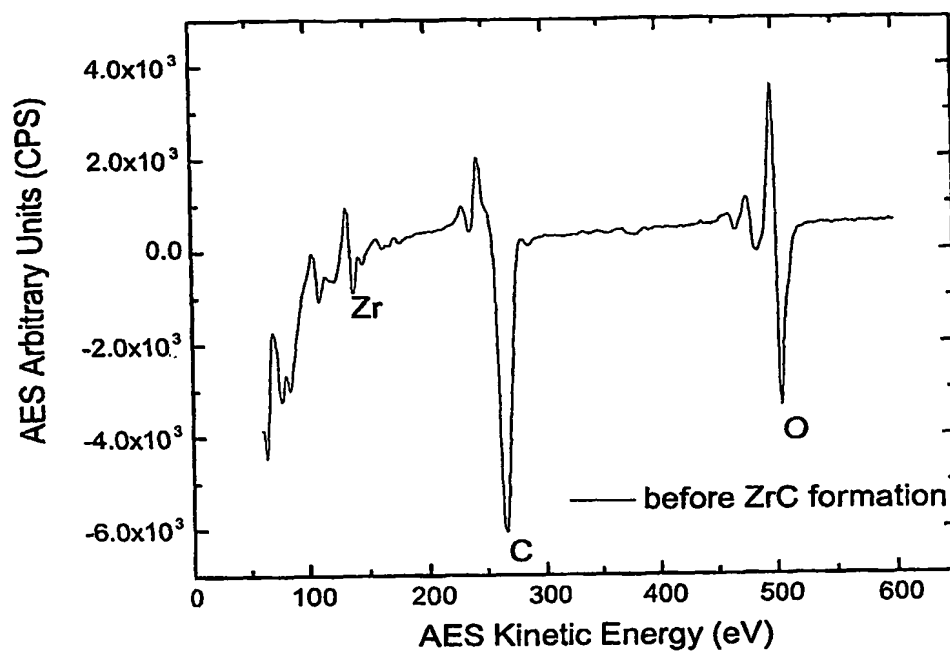


FIG. 32

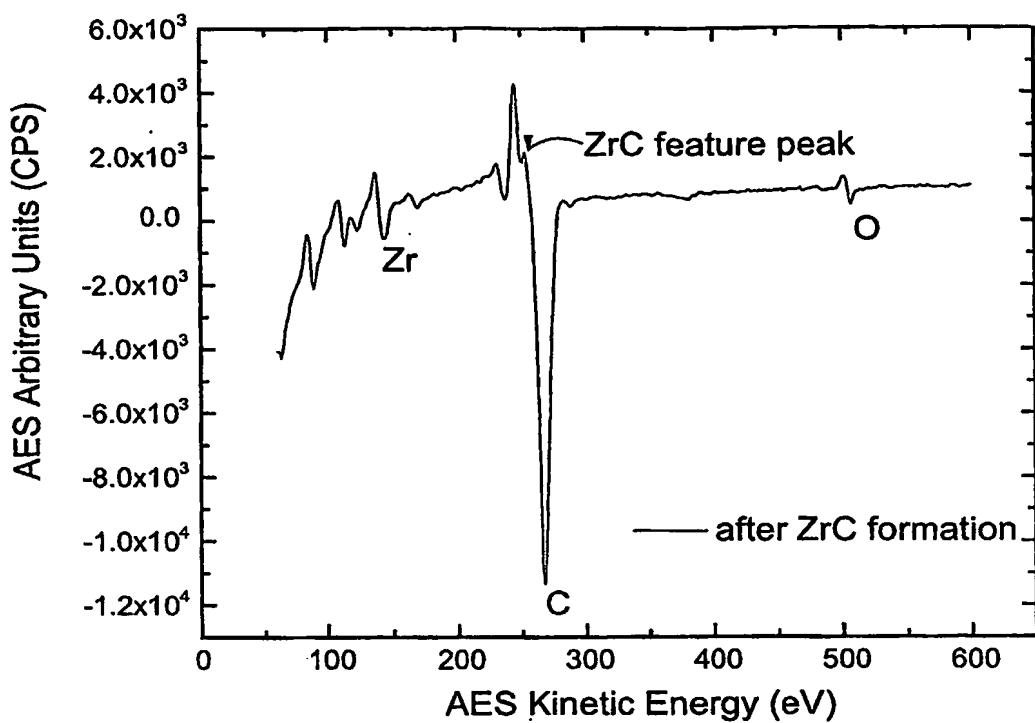


FIG. 33

34/36

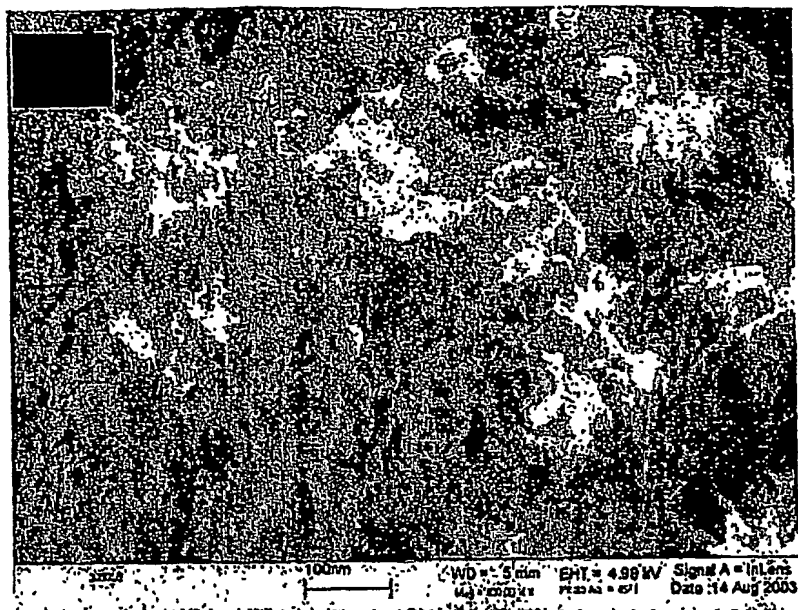


FIG. 34A



FIG. 34B

35/36

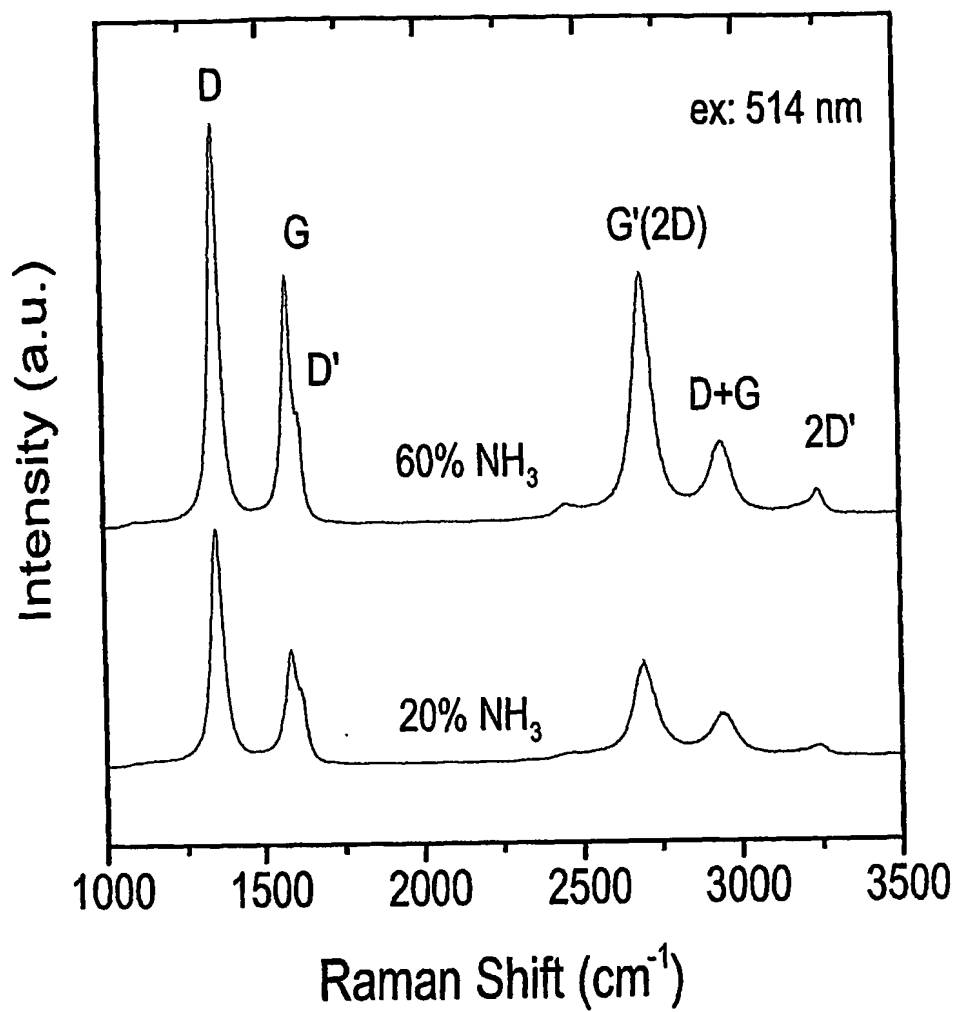


FIG. 35

36/36

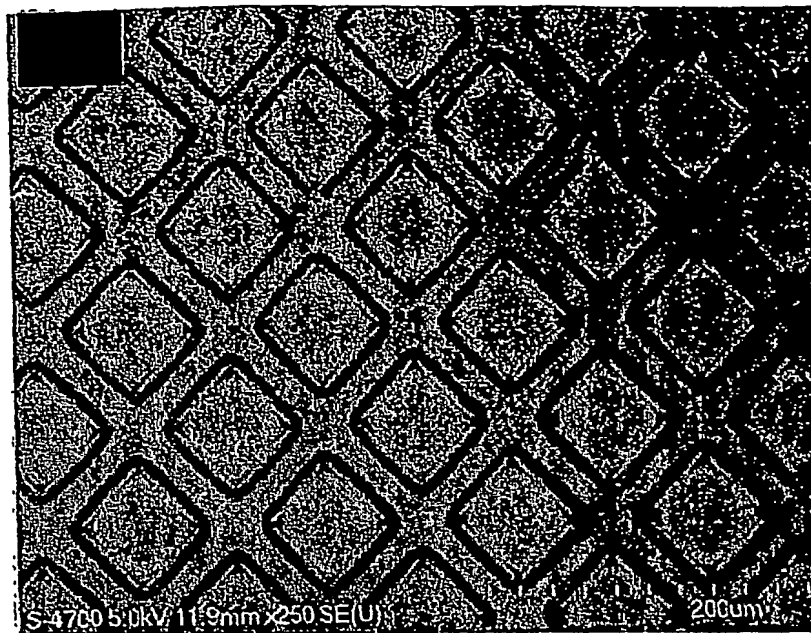


FIG. 36A

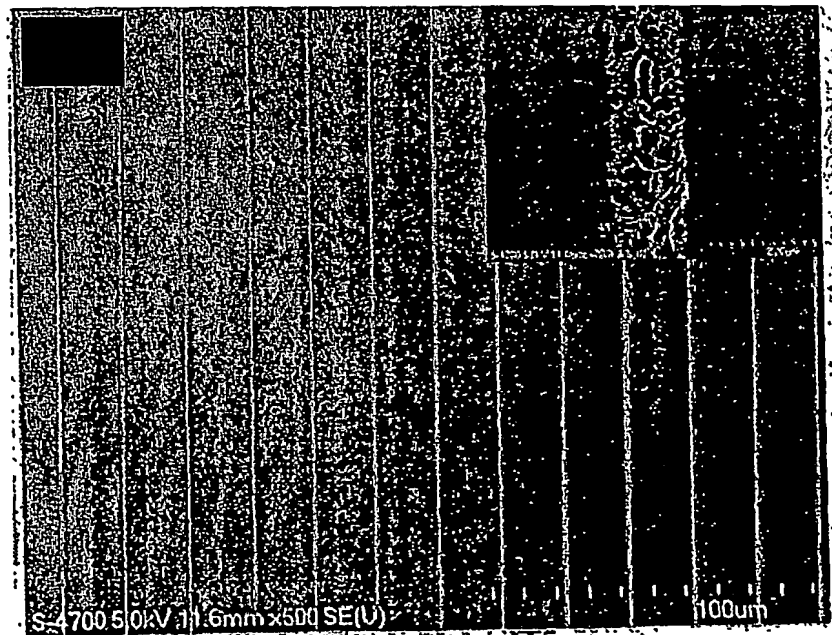


FIG. 36B

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